



	2024				DISU221		01
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	( 09:00 18:00 ) - [510 ]						

Coater, Developer, Exposure #

E-Beam Lithography #

Mask Aligner #

ICP Etcher #

Etching on pattern depth #

PR asher 02Plasma #

Ashing #

Furnace #

RTP #

PVD #

PE-CVD SiO2 #

LP-CVD Poly si #

ALD AL2O3